

United States Patent and Trademark Office

UNITED STATES DEPARTMENT OF COMMERCE United States Patent and Trademark Office Address: COMMISSIONER FOR PATENTS P.O. Box 1450 Alexandria, Virginia 22313-1450 www.uspto.gov

APPLICATION NO.	FILING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO.
09/720,761	03/26/2001	Franz Laermer	10191/1629	5642
26646 7	590 12/30/2004		EXAMINER	
KENYON & KENYON ONE BROADWAY			CHEN, KIN CHAN	
NEW YORK,			ART UNIT	PAPER NUMBER
•			1765	

DATE MAILED: 12/30/2004

Please find below and/or attached an Office communication concerning this application or proceeding.

				!		
		Application No.	Applicant(s)	V		
	are a vi	09/720,761	LAERMER ET AL.			
	Office Action Summary	Examiner	Art Unit			
		Kin-Chan Chen	1765			
Period fo	The MAILING DATE of this communication a or Reply	appears on the cover she t with the	correspondence address	-		
THE - Exte after - If the - If NC - Failt Any	ORTENED STATUTORY PERIOD FOR REI MAILING DATE OF THIS COMMUNICATION insions of time may be available under the provisions of 37 CFR SIX (6) MONTHS from the mailing date of this communication. It is period for reply specified above is less than thirty (30) days, and period for reply is specified above, the maximum statutory periure to reply within the set or extended period for reply will, by state reply received by the Office later than three months after the material part of the material process. See 37 CFR 1.704(b).	N. 1.136(a). In no event, however, may a reply be tir reply within the statutory minimum of thirty (30) day od will apply and will expire SIX (6) MONTHS from tute, cause the application to become ABANDONE	mely filed ys will be considered timely. the mailing date of this communication ED (35 U.S.C. § 133).	n.		
Status						
1)[🗆	Responsive to communication(s) filed on 19	November 2004				
		his action is non-final.				
3)□	Since this application is in condition for allow closed in accordance with the practice under	vance except for formal matters, pro		;		
Disposit	ion of Claims					
5)⊠ 6)⊠ 7)□	Claim(s) 19,21-24 and 27-40 is/are pending 4a) Of the above claim(s) is/are withd Claim(s) 19,21-24,27-36,39 and 40 is/are al Claim(s) 37 and 38 is/are rejected. Claim(s) is/are objected to. Claim(s) are subject to restriction and	lrawn from consideration. lowed.				
Applicat	ion Papers					
9)[The specification is objected to by the Exami	iner.				
10)	☐ The drawing(s) filed on is/are: a)☐ accepted or b)☐ objected to by the Examiner.					
	Applicant may not request that any objection to the		` '			
44)["]	Replacement drawing sheet(s) including the com		·	1).		
11)[The oath or declaration is objected to by the	Examiner. Note the attached Office	: Action or form PTO-152.			
Priority (ınder 35 U.S.C. § 119					
a)i	Acknowledgment is made of a claim for forei All b) Some * c) None of: 1. Certified copies of the priority docume 2. Certified copies of the priority docume 3. Copies of the certified copies of the priority docume application from the International Bure See the attached detailed Office action for a light	ents have been received. ents have been received in Applicationity documents have been received and (PCT Rule 17.2(a)).	ion No ed in this National Stage			
		·				
_		·				
Attachmen	t(s) e of References Cited (PTO-892)	лП .	(DTO 442)			
	e of References Cited (PTO-892) e of Draftsperson's Patent Drawing Review (PTO-948)	4) 🔲 Interview Summary Paper No(s)/Mail D				
3) 🔲 Infori	mation Disclosure Statement(s) (PTO-1449 or PTO/SB/0 r No(s)/Mail Date	()8) 5) ☐ Notice of Informal F 6) ☐ Other:	Patent Application (PTO-152)			

DETAILED ACTION

Claim Rejections - 35 USC § 103

- 1. The following is a quotation of 35 U.S.C. 103(a) which forms the basis for all obviousness rejections set forth in this Office action:
 - (a) A patent may not be obtained though the invention is not identically disclosed or described as set forth in section 102 of this title, if the differences between the subject matter sought to be patented and the prior art are such that the subject matter as a whole would have been obvious at the time the invention was made to a person having ordinary skill in the art to which said subject matter pertains. Patentability shall not be negatived by the manner in which the invention was made.
- 2. Claims 37 and 38 are rejected under under 35 U.S.C. 103(a) as obvious over Sony (EP 0 414 372 A2).

Sony teaches a method of anisotropic plasma etching a defined structure in as silicon substrate using a process gas. Sony teaches adding a fluorine-delivering etching gas to the process gas. The fluorine-delivering etching gas may include CIF₃. Sony also teaches that plasma in a wide range of gas mixtures including SiF₄, Cl₂/ O₂, and Cl₂/ N₂ can be used to supply fluorine atoms for selective isotropic silicon etching. The said gas mixtures can deposit protective layer (so-called precipitating at least one passivating material in the instant claims), (col.1 (page 2), lines 41-48; Col. 4 (page 3), lines 7-17). Sony teaches using dry etching to from a desired configuration in the silicon substrate. Sony is not particular about the desired configuration. Hence, it would have been obvious to one with ordinary skilled in the art to etch a laterally defined structure because it is one of the most popular structure in the semiconductor device fabrication.

Response to Arguments

3. Applicant's arguments (November 19, 2004) with respect to claims 37-40 have been fully considered but they are not persuasive.

Applicant has argued that the prior art teaches using Cl_2/O_2 or $SiCl_4 / O_2$ not teaches the addition of compounds including oxygen. It is not persuasive. Cl_2/O_2 or $SiCl_4 / O_2$ of the prior art comprises oxygen. Furthermore, applicant's claimed invention does not preclude Cl_2 or $SiCl_4$ in the compound.

Conclusion

- 4. Claims 19, 21-24, 27-36, 39, and 40 are allowed.
- 5. The prior art made of record and not relied upon is considered pertinent to applicant's disclosure. Pu et al. (US 5,843,847; col. 1, line 62 through col. 2, line 4) teaches that fluorocarbon gas containing C_2F_6 forms polymeric by products that deposits as a passivating layer.
- 6. Any inquiry concerning this communication or earlier communications from the examiner should be directed to Kin-Chan Chen whose telephone number is (571) 272-1461. If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Nadine Norton can be reached on (571) 272-1465. The fax phone number for the organization where this application or proceeding is assigned is 703-872-9306.

Application/Control Number: 09/720,761

Art Unit: 1765

Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see http://pair-direct.uspto.gov. Should you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free).

December 23, 2004

Kin-Chan Chen Primary Examiner Art Unit 1765 Page 4

K-C C